

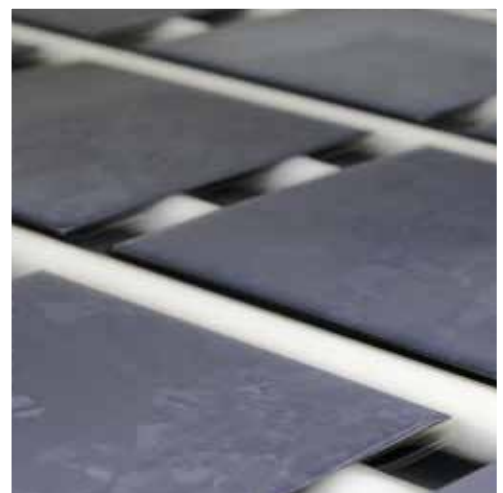


# RCT i-Side

## RCT i-Side is part of the RCT Inline machine family.

RCT i-Side with its improved process sequence enables high efficiency cell technologies such as PERC, n-type or Bifacial. RCT i-Side polishes wafer with highest reflectivity at cost effective etch depths.

It is optimized for lowest CoO by low chemical consumption, stable processes and small footprint.

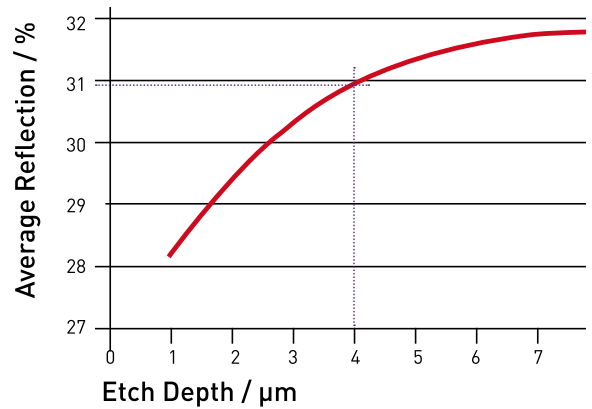


RCT i-Side for single-side junction isolation or polishing

# Highlights

- ✦ Improved hydrodynamics of etch bath allows higher reflectivity at lower etch depth, saving 60% of consumables.
- ✦ Patented process sequence with preTreatment, Rinse and junction isolation / polishing.
- ✦ Advanced alkaline cleaning design to avoid KOH contamination.
- ✦ Surface near frequent chemical exchange for high-performance metal impurity cleaning.
- ✦ Unique quick-lock system of spray bars for easy and fast maintenance.
- ✦ Up to 30% reduced DI water consumption due to improved rinse bath performance.

optimum COO at reduced etch depth

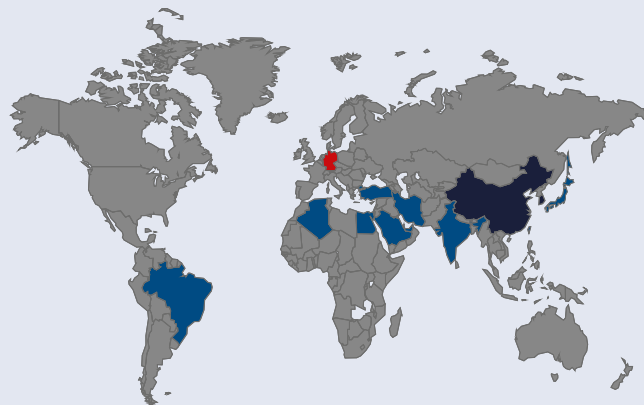


textured wafer vs. polished wafer after 4 $\mu\text{m}$  etch depth

## RCT i-Side Technical Data

Process	Inline junction isolation / polishing and cleaning
Throughput	3,600 w/h gross, 5 lanes
Conveyor speed	0.5 – 2.5 m/min, nominal 2.1 m/min
Dimensions	8880 x 2200 x 2120 mm <sup>3</sup> (L x W x H)
Wafer size	156 x 156 $\pm$ 0.5mm / 156.75 x 156.75 $\pm$ 0.25mm, $\geq$ 150 $\mu\text{m}$
Etch depth range	0.7 – 6 $\mu\text{m}$
Bath lifetime	> 1,500,000 wafers
Breakage Rate	< 0.05%

RCT Solutions –  
where we are



### Headquarter

Constance, Germany

### Affiliates & Offices

China

Taiwan

Korea

### Sales Partner

RCT Solutions GmbH  
Line-Eid-Straße 1  
D-78467 Konstanz, Germany  
info@rct-solutions.com  
www.rct-solutions.com

苏州瑞客特自动化设备有限公司  
中国江苏省苏州市高新区许墅关开发区石阳路17号  
RCT Automation Equipment (Suzhou) Co, Ltd.  
sales@rct-solutions.com  
www.rct-solutions.com